Application No.: 10/077,784 Docket No.: M4065.0482/P482

73. The memory card of claim 72, further comprising:

a bottom electrode attached to a second surface of said layer.

74. The memory card of claim 73, wherein said bottom electrode is a common electrode for said memory storage area.

75. The memory card of claim 72, wherein said memory storage areas comprise \checkmark at least one of temporary and permanent memory storage.

- 76. The memory card of claim 72, wherein said layer comprises chalcogenite.
- 77. The memory card of claim 72, wherein said layer comprises between 20-30 percent germanium, between 70 and 80 percent selenium, and is doped with silver.
- 78. The memory card of claim 73, wherein said bottom electrode further comprises a conductor such as silver.
- 79. The memory card of claim 73, wherein said bottom electrode further comprises a conductor such as tungsten.
- 80. The memory card of claim 72, wherein said layer further comprises alignment areas.
- 81. The memory card of claim 80, wherein said alignment areas are formed as memory storage areas programmed with a pattern.
- 82. The memory card of claim 81, wherein said alignment areas are formed as alignment marks.
- 83. The memory card of claim 72, wherein said memory card has active circuit elements.

/g/

Application No.: 10/077,784

Docket No.: M4065.0482/P482

(h)

84. The memory card of claim 72, wherein at least some of said memory storage areas are non volatile.

85. The memory card of claim 72, wherein said first surface of said card is adapted to directly contact said conductive elements.